



501.37465CC8

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Y. TANABE, et al.

Serial No: 10/774,406

Filed: February 10, 2004

Title: METHOD FOR FABRICATING SEMICONDUCTOR
INTEGRATED CIRCUIT DEVICE

Group: 2813

Examiner: Thanhha S. PHAM

COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450
Box Issue Fee

April 4, 2005

Sir:

The Examiner's Statement of Reasons for Allowance set forth in Item 2 on pages 2 and 3 of the Notice of Allowability attached to the Notice of Allowance mailed January 3, 2005, is noted. This Statement sets forth that the recorded prior art "fails to disclose or suggest a combination of the processing steps for fabricating a semiconductor integrated circuit device as recited in the base claim 1", and then sets forth specified steps. Note that, in addition to the processing steps as set forth by the Examiner in Item 2, claim 1 also recites a step of introducing a wafer into a single wafer heat treatment chamber of an oxidation furnace; and, after performing the thermal oxidation treatment, replacing the wet oxidative atmosphere, in the heat treatment chamber where the wafer has been introduced, with nitrogen gas. Thus, more precisely, where the Examiner refers to the "combination of the process

steps" in the base claim 1, the Statement by the Examiner should also include the process step of introducing the wafer into the single wafer heat treatment chamber of the oxidation furnace, and replacing the wet oxidative atmosphere with nitrogen gas, as mentioned previously.

The undersigned also directs the Examiner's attention to the concurrently filed Information Disclosure Statement Under 37 C.F.R. § 1.97 and 1.98. It is respectfully submitted that the present filing of this Information Disclosure Statement and documents enclosed therewith satisfies applicable requirements of 37 C.F.R. §1.97 and 1.98. Consideration of the submitted documents, and, subsequent thereto, issuance of a U.S. patent based upon the above-identified application in due course, are respectfully requested.

To the extent necessary, Applicants petition for an extension of time under 37 CFR §1.136. Please charge any shortage in the fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account No. 01-2135 (Case No. 501.37465CC8) and please credit any excess fees to such deposit account.

Respectfully submitted,



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WIS/kmh

Attachments